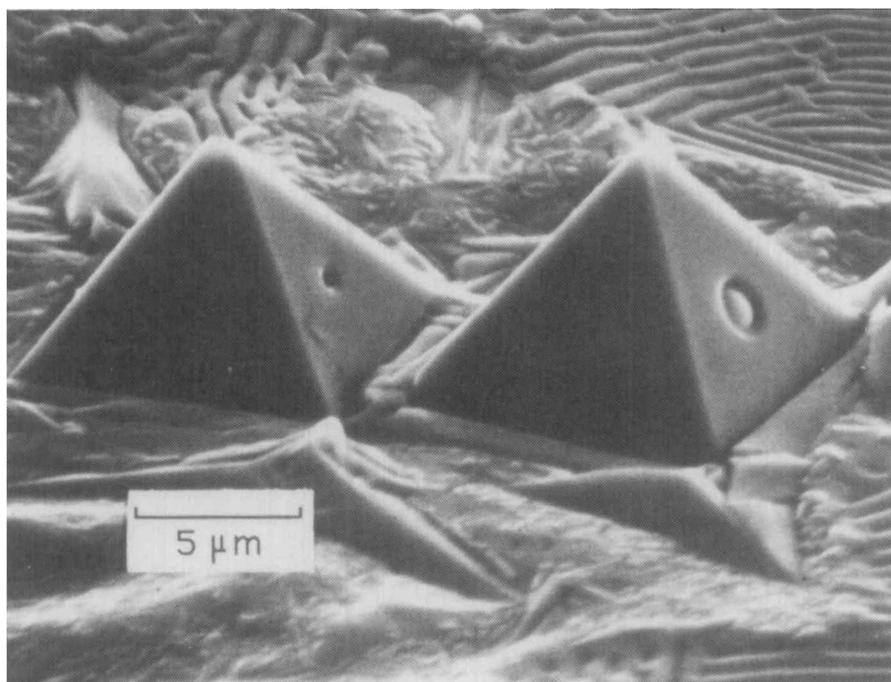


Editor's Choice

Figures appearing in the EDITOR'S CHOICE are those arising from materials research which strike the editor's fancy as being aesthetically appealing and eye-catching. No further criteria are applied and none should be assumed. When taken out of context, such figures often evoke images beyond and unrelated to the original meaning. Submissions of candidate figures are welcome and should include a complete source citation, a photocopy of the report in which it appears (or will appear), and a reproduction-quality original drawing or photograph of the figure in question.



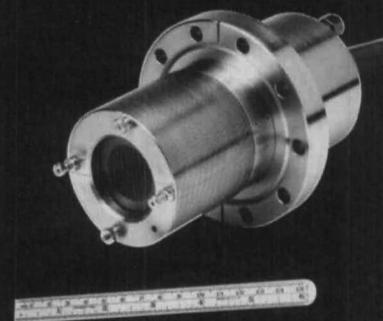
The EDITOR'S CHOICE for this issue appears to be an aerial photograph of huge ancient pyramids set among desert dunes in the late afternoon. The scale marker, of course, informs us that we are really viewing a micrograph of growths on a material surface. These crystallites were observed on the inner surface of a shrinkage cavity formed on solidification of a nickel-tin eutectic alloy sphere levitated in microgravity aboard the space shuttle. The precise origin of these crystals, the composition of which differed from the bulk alloy, could not be determined by the authors, T.J. Piccone et al., who reported their study in *Materials Processing in the Reduced Gravity Environment of Space*, edited by R.H. Doremus and P.C. Nordine (Mater. Res. Soc. Proc. 87, Pittsburgh, PA, 1987) p. 47.

ERRATA

The photo showing the structure of a high temperature superconductor (May/June, Vol. XII No. 4, p. 15) should have been credited to Argonne National Laboratory.

Symposium J Organizers (May/June, Vol. XII No. 4, p. 77) should have been identified as follows (left to right): H. King, G.E. Brown, Jr., and R. Jeanloz.

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